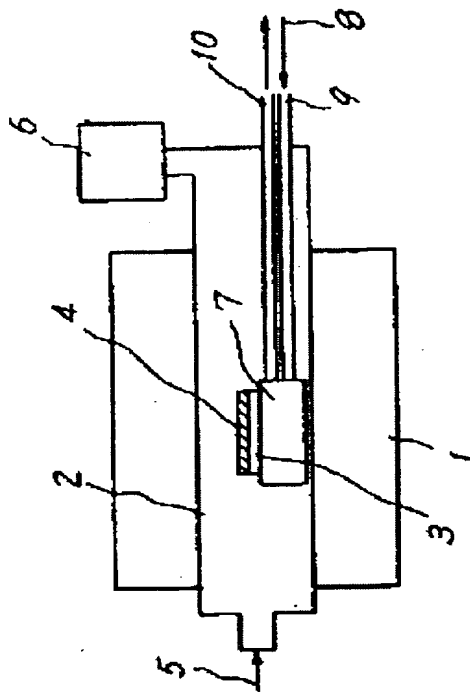


MANUFACTURE OF OPTICAL WAVEGUIDE FILM

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Abstract of JP58030710

PURPOSE: To efficiently obtain a uniform optical waveguide film by placing a substrate for forming a porous oxide film in a reaction tube and by oxidizing starting materials for forming oxides at a high temp. while keeping the substrate at a temp. below the oxidation temp. in the reaction tube. **CONSTITUTION:** A reaction tube 2 is put in a tubular electric furnace 1, a substrate cooler 7 is placed in the tube 2, and a substrate 3 is mounted on the cooler 7. By blowing a gas 8 for cooling from a duct 9, the cooler 7 is cooled to make the temp. of the substrate 3 constant. At this time, the gas 8 is intermittently discharged from a duct 10 to intermittently keep the substrate 3 at a constant temp. A gas saturated with $TiCl_4$, a gas saturated with $SiCl_4$ and O_2 as starting materials 5 for forming glass are introduced into the tube 2 and heated to 1,400 deg.C to cause oxidation. At this time, by keeping the substrate 3 at 1,200 deg.C, a porous film 4 of TiO_2 - SiO_2 composite oxide glass is uniformly formed. The film is melted by heating to 1,400 deg.C to obtain a prescribed optical waveguide film.



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